

ABSTRACT

Fe-Pt-BASED SPUTTERING TARGET WITH DISPERSED C GRAINS

5 A sintered compact sputtering target in which a composition ratio based on atomicity is represented by a formula of $(\text{Fe}_{100-X}\text{-Pt}_X)_{100-A}\text{-C}_A$ (provided A is a number which satisfies $20 \leq A \leq 50$ and X is a number which satisfies $35 \leq X \leq 55$), wherein C grains are finely dispersed in an alloy, and the relative density is 90% or higher.

10 An object of this invention is to enable the production of a magnetic thin film with granular structure without using an expensive simultaneous sputtering device, as well as provide a high-density sputtering target capable of reducing the amount of particles generated during sputtering.

[Selected Drawing] Fig. 1